

filed 7/25/03

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

SYSTEM AND METHOD OF ALTERING A VERY SMALL SURFACE AREA BY MULTIPLE CHANNEL PROBE

Application Number : 10 / 604,486

Confirmation Number:

First Named Applicant: Hendrik Hamann

Attorney Docket Number: FIS920020170US1

Art Unit: 1765

Examiner: Alanko

Search string: (5865978 or 6002471 or 4880496 or 6078055).pn

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
VKE	1	5865978	1999-02-02	Cohen		205	118
	2	6002471	1999-12-14	Quake		356	73
	3	4880496	1989-11-14	Nebenzahl, et al.		216	93
↓	4	6078055	2000-06-20	Bridger, et al.	✓	250	442.2

Signature

Examiner Name	Date
Hendrik Hamann	6/20/05

<p style="text-align: center;">INFORMATION DISCLOSURE CITATION <small>(use several sheets if necessary)</small></p> <p style="text-align: right;">filed 8/14/03</p> <p style="text-align: center;">(SUS 11 2003)</p>		Docket Number (Optional) FIS920020170US1	Application Number 10/604,486
		Applicant(s) Hendrik F. Hamann et al.	
		Filing Date 07/25/2003	Group Art Unit 1765
*EXAMINER INITIAL <i>H/Cf</i>	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
	<p>A Nanoplotter with Both Parallel and Serial Writing Capabilities, Seunghun Hong and Chad A. Mirkin, Science Magazine, Vol. 288, June 9, 2000, pp 1808 - 1811.</p>		
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EXAMINER <i>Druta Hamann</i>	DATE CONSIDERED <i>6/20/05</i>		
<p>*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>			

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		Filing Date 07/25/2003	Group Art Unit
*EXAMINER INITIALS <i>AH</i>	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
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EXAMINER <i>Smita Hamann</i>	DATE CONSIDERED <i>6/20/05</i>		
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EXAMINER <i>Sunita Hamann</i>	DATE CONSIDERED <i>6/20/05</i>		
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